

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: OHSAWA, Youichi et al  
Appl. No.: NEW Group:  
Filed: February 12, 2004 Examiner:  
For: NOVEL SULFONYLDIAZOMETHANES, PHOTOACID  
GENERATORS, RESIST COMPOSITIONS, AND  
PATTERNING PROCESS

INFORMATION DISCLOSURE STATEMENT  
(SUBMISSION CONCURRENT WITH THE  
FILING OF A NEW PATENT APPLICATION)

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

February 12, 2004

Sir:

Pursuant to 37 C.F.R. §§ 1.97 and 1.98, applicant(s) hereby submit(s) an Information Disclosure Statement for consideration by the Examiner.

I. LIST OF PATENTS, PUBLICATIONS OR OTHER INFORMATION

The patents, publications, or other information submitted for consideration by the Office are listed on PTO-1449, attached hereto.

II. COPIES

- a. ☐ This application was filed before June 30, 2003. Accordingly, submitted herewith is a legible copy of (i) each U.S. and foreign patent; (ii) each publication or that portion which caused it to be listed; and (iii) all other information or that portion which caused it to be listed.
- b. ☒ This application was filed on or after June 30, 2003. Accordingly, copies of cited US patents and patent application publications therefore are not included. Copies of foreign patent documents and non-patent literature are included.

- c. ☐ This application is a National Phase of a PCT application. Some or all of the documents listed on the PTO-1449 are not enclosed because they were cited in the International Search Report and copies should be forwarded from the International Search Authority. If copies are needed, please contact the undersigned.

III. CONCISE EXPLANATION OF THE RELEVANCE  
(check at least one box)

- a. ☒ **DOCUMENTS IN THE ENGLISH LANGUAGE**

The patents, publications, or other information listed on the attached PTO 1449 are in the English language and therefore, do not require a statement of relevancy.

- b. ☒ **DOCUMENTS NOT IN THE ENGLISH LANGUAGE**

A concise explanation of the relevance of all patents, publications, or other information listed that is not in the English language is as follows:

The relevancy of the Japanese language documents can be determined from a review of the English language Abstract attached thereto.

- c. ☐ **ENGLISH LANGUAGE SEARCH REPORT**

An English language version of the search report or action that indicates the degree of relevance found by the foreign office is attached, thereby satisfying the requirement for a concise explanation. See MPEP 609(III) (A) (3).

- d. ☒ **OTHER**

The following additional information is provided for the Examiner's consideration.

JP 3-103854 corresponds to US Patent No. 5,338,641  
JP 10-90884 corresponds to US Patent Nos.  
5,945,517/ US Patent 5,908,730  
JP 8-123032 corresponds to US Patent Nos.  
5,558,971/ US Patent 5,558,976  
JP 11-190904 corresponds to US Patent No.  
6,136,502

FEES

This Information Disclosure Statement is being filed concurrently with the filing of a new patent application; therefore, no fee is required.

If the Examiner has any questions concerning this IDS, he/she is requested to contact the undersigned. If it is determined that this IDS has been filed under the wrong rule, the PTO is requested to consider this IDS under the proper rule and charge the appropriate fee to Deposit Account No. 02-2448.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under § 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By   
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GMM/smt  
0171-1063P

Attachment(s): ☒ Form PTO-1449(s)  
☒ Documents  
☐ Foreign Search Report  
☐ Fee  
☐ Other: \_\_\_\_\_

(Rev. 09/30/03)

Form PTO-1449				ATTY. DOCKET NO. 0171-1063P		APPLICATION NO. NEW	
<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b> (Use several sheets if necessary)				APPLICANT OHSAWA, Youichi et al			
				FILING DATE February 12, 2004		GROUP	

  

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	US 2,354,229		1994-07-25	Walter et al.			
	US 6,261,738	B1	2001-07-17	Asakura et al.			
	US 6,004,724	A	1999-12-21	Yamato et al.			
	US 5,338,641		1994-8-16	Pawlowski et al.			

  

FOREIGN PATENT DOCUMENTS									
	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
	JP	3-103854	A	1991-04-30	JAPAN			ABS	
	JP	10-90884	A	1998-04-10	JAPAN			ABS	
	JP	2001-55373	A	2001-02-27	JAPAN			ABS	
	JP	2001-106669	A	2001-04-17	JAPAN			ABS	
	JP	8-123032	A	1996-05-17	JAPAN			ABS	
	JP	11-72921	A	1999-03-16	JAPAN			ABS	
	JP	11-38604	A	1999-02-12	JAPAN			ABS	
	JP	6-266112	A	1994-09-22	JAPAN			ABS	
	JP	4-211258	A	1992-08-03	JAPAN			ABS	

  

OTHER DOCUMENTS	
(Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)	
	Leo A. Paquette, J. Am. Chem. Soc., Vol 86, pages 4383-4385, (October 20, 1964)
	Walter et al., J. Am. Chem. Soc., Vol. 67, pages 655-657, (April 1945)
	Wagner et al., Synthetic Organic Chemistry, John Wiley & Sons, Inc., 1965, pages 778-781
	Arimitsu et al., J. Photopolym. Sci. and Tech., Effect of Phenolic Hydroxyl Residues on the Improvement of Acid-Proliferation-Type Photoimaging Materials., page 29 & 30 (1996)
	Arimitsu et al., J. Photopolym. Sci. and Tech., Sensitivity Enhancement of Chemical-Amplification-Type Photoimaging Materials By Acetoacetic Acid Derivatives, Vol 8, Number 1, pages 43 & 44, Number 1 (1995)
	Kudo et al., J. Photopolym. Sci. and Tech., Enhancement of the Sensitivity of Chemical-Amplification-type Photoimaging Materials by $\beta$ -Tosyloxyketone Acetals, Vol. 8, Number 1 pages 45-46, (1995)

  

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

GMA

GMM/smt

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<b>U.S. PATENT DOCUMENTS</b>									
EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
	US 5,945,517		1999-8-31	Nitta et al.					
	US 5,908,730		1999-6-1	Nitta et al.					
	US 5,558,971		1996-9-24	Urano et al.					
	US 6,136,502		2000-10-24	Satoshi et al.					
	US 5,558,976		1996-9-26	Urano et al.					
<b>FOREIGN PATENT DOCUMENTS</b>									
	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
	JP	2000-344836	A	2000-12-12	JAPAN			ABS	
	JP	11-190904	A	1999-7-13	JAPAN			ABS	
	JP	2906999	B2	1999-4-2	JAPAN			ABS	
	JP	2000-314956	A	2000-11-14	JAPAN			ABS	
	JP	9-301948	A	1997-11-25	JAPAN			ABS	
	JP	9-95479	A	1997-4-8	JAPAN			ABS	
	JP	9-230588	A	1997-9-5	JAPAN			ABS	
	JP	9-208554	A	1997-8-12	JAPAN			ABS	
<b>OTHER DOCUMENTS</b> (Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.									
EXAMINER					DATE CONSIDERED				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									